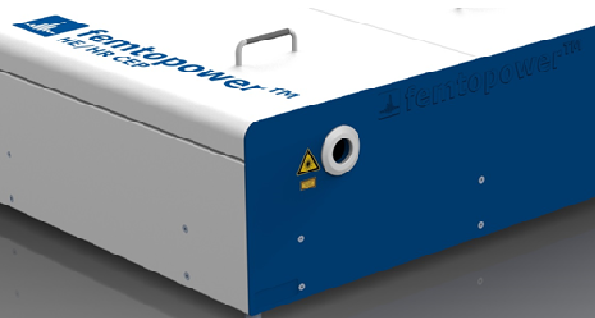
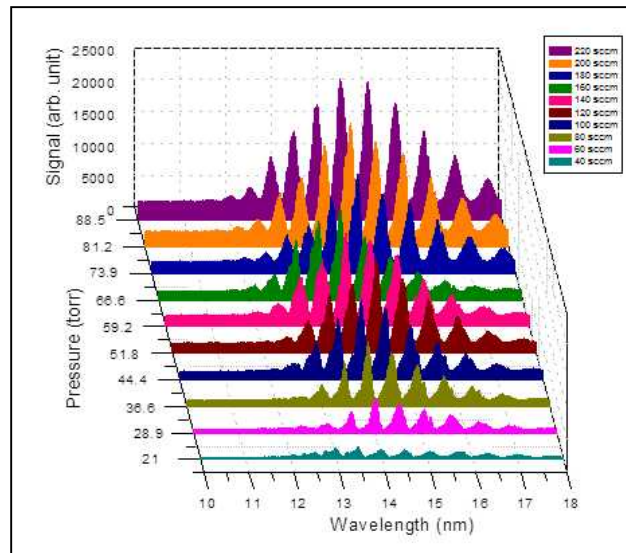


레이저스펙트라

eXtra - eXtreme UV Light Source laser-like spectra 10-30nm

The eXtra is an extreme UV light source which provides the laser-like (coherent) spectra between 10nm and 30nm, based on the high harmonic generation (HHG) in a laser-produced plasma. The eXtra system is configured as a table-top solution with a kHz rep rate, femtosecond Ti:sapphire laser at a wavelength around 800nm, and a HHG gas chamber under vacuum. The laser pulses are focused with intensity of 10^{14} - 10^{15} W/cm² into the patent-pending gas cell in the chamber. The generated EUV spectra are separated from the laser wavelength with an appropriate combination of the beamsplitters and filters. The eXtra-13.5 is highly optimized for a spectra 13.5nm for the actinic inspection and metrology applications in the EUV lithography.

- Coherent EUV imaging
- Litho inspection & metrology
- Photoelectron spectroscopy
- Attosecond pulse generation



Turnkey EUV Light Solution
fs lasers, EUV generation, EUV optics
EUV spectrometers, EUV detectors

For more information, please contact :

레이저스펙트라
Laser Spectronix

Byucksan Digital Valley 6-406,
Gasam-dong, Geumcheon-gu,
Seoul, KOREA

Tel: (02) 2627-3121
Fax: (02) 2627-3120
email: laser@laser.co.kr
home: www.laser.co.kr